REMARKS

Claims 1-15 are all the claims pending in the application. Claims 1-5, 7, 11 and 12 are rejected. Claims 6, 8-10 and 13-15 are objected to but would be allowable if placed into independent form. Claims 1 and 2 are amended. New claims 16-24 are added.

The amendment to claim 1 is based on the description related to Example 1 of page 21, line 9 from the bottom through page 24, line 11 from the bottom of the original specification, especially, on the description of page 24, line 1 through page 24, line 11 from the bottom of the specification. The amendment to claim 1 is also based on the description related to Example 2 of page 24, line 10 from the bottom through page 26, line 3 of the original specification, especially, on the description of page 25, line 9 from the bottom through page 26, line 3 of the original specification.

The amendment to claim 2 is based on the description related to Example 5 of page 27, line 1 through page 27, line 7 from the bottom of the original specification.

New claims 16 and 17 are based on the description of page 3, lines 14-18 of the original specification and Examples 1-5.

The new claims 18 and 20 are based on the description of page 9, lines 1-5 of the original specification.

New claims 19 and 21 are based on the description of page 18, lines 4-6 of the original specification.

New claim 22 is based on the description of amended claim 1 and on the description of page 17, lines 2-10 of the instant specification.

The new claims 23 and 24 are based on the description of page 18, lines 4-6 of the original specification.

Claim Rejections - 35 U.S.C. § 103

Claims 1-5, 7, 11 and 12 are rejected under 35 U.S.C. § 103(a) as being unpatentable over Hata et al (JP 63-114866) in view of Takeuchi et al (2002-0179576). This rejection is traversed for at least the following reasons.

Amendment Under 37 C.F.R. § 1.111 U.S. Application No. 10/809,419

Claim 1

Claim 1 has been amended. Neither Hata et al nor Takeuchi et al teach, suggest or disclose "said method producing, as said glass substrate, a glass substrate for an EUV (extreme ultra violet) mask blank and comprising said flatness control step, said acid treatment step, and said polishing step carried out in this order to thereby make the surface of the glass substrate have a flatness and a surface roughness required to the glass substrate for the EUV mask blank," as now recited in amended claim 1. With the invention as claimed, it is possible to produce a glass substrate for an EUV mask blank by carrying out the flatness control step, the acid treatment step, and the polishing step in this order, to thereby make the surface of the glass substrate have a flatness and a surface roughness required of the glass substrate for the EUV mask blank

Claim 2

Furthermore, Neither Hata et al nor Takeuchi et al teach, suggest or disclose "said method producing, as said glass substrate, a glass substrate for an EUV (extreme ultra violet) mask blank and comprising said flatness control step, said alkali treatment step, and said polishing step carried out in this order to thereby make the surface of the glass substrate have a flatness and a surface roughness required to the glass substrate for the EUV mask blank," as now recited in amended claim 2. With the invention as claimed, it is possible to produce a glass substrate for an EUV mask blank by carrying out the flatness control step, the alkali treatment step, and the polishing step in this order, to thereby make the surface of the glass substrate have a flatness and a surface roughness required of the glass substrate for the EUV mask blank.

Claim 22

Likewise, neither Hata et al nor Takeuchi et al teach, suggest or disclose "said method producing, as said glass substrate, a glass substrate for an EUV (extreme ultra violet) mask blank and comprising said flatness control step, said acid or alkali treatment step, and said polishing step carried out in this order to thereby make the surface of the glass substrate have a flatness and a surface roughness required to the glass substrate for the EUV mask blank" in new claim 22.

Since this express limitation is not present in the references alone or in combination, Applicants submit that amended claims 1 and 2 and new claim 22 are patentable. Amendment Under 37 C.F.R. § 1.111 U.S. Application No. 10/809,419

Claims 3-5, 7, 11, 12, 16-21, 23 and 24

Furthermore, Applicants respectfully submit that the remaining claims are also patentable because they depend from the patentable claims 1, 2, and 22.

In view of the above, reconsideration and allowance of this application are now believed to be in order, and such actions are hereby solicited. If any points remain in issue which the Examiner feels may be best resolved through a personal or telephone interview, the Examiner is kindly requested to contact the undersigned at the telephone number listed below.

The USPTO is directed and authorized to charge all required fees, except for the Issue Fee and the Publication Fee, to Deposit Account No. 19-4880. Please also credit any overpayments to said Deposit Account.

Respectfully submitted,

/Alan J. Kasper/

Alan J. Kasper Registration No. 25,426

SUGHRUE MION, PLLC Telephone: (202) 293-7060 Facsimile: (202) 293-7860

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Date: May 14, 2007